

## **Removal of Fine Particle using SAPS Technology and Functional Water**

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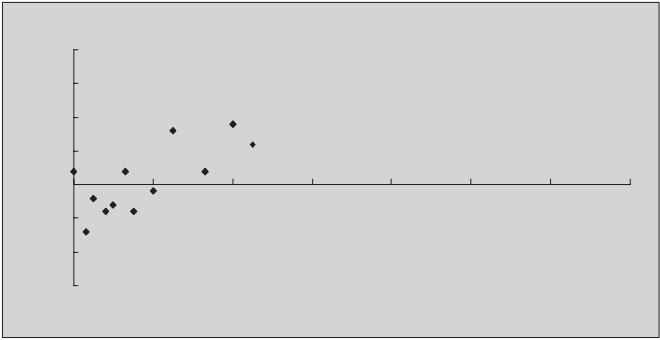
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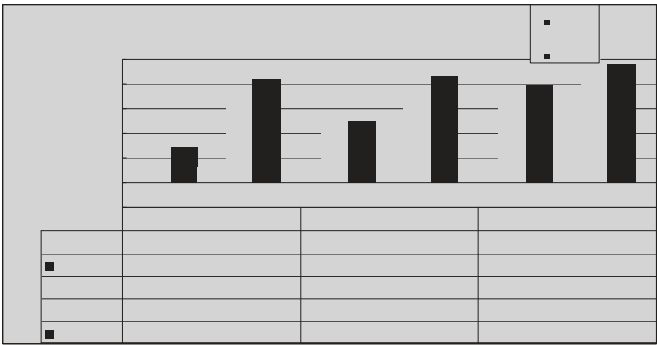
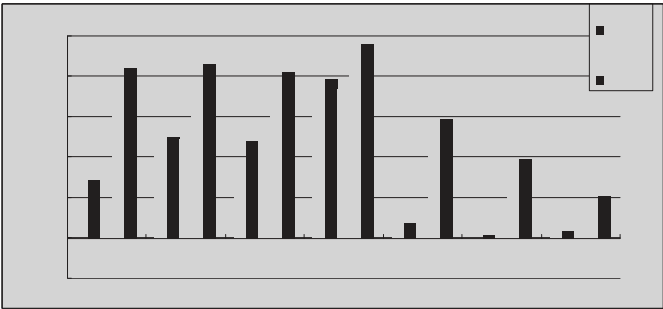
**Keywords:** Particle removal, Functional water, SAPS megasonic technology

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| Term                | t Ratio   |  |  |  |  |  |
|---------------------|-----------|--|--|--|--|--|
| N2(3,14)            | -1.588785 |  |  |  |  |  |
| NH4OH*MegaPower     | 1.430211  |  |  |  |  |  |
| N2*NH4OH            | 1.328053  |  |  |  |  |  |
| MegaPower(5,20)     | -0.929195 |  |  |  |  |  |
| NH4OH(5,30)         | -0.668952 |  |  |  |  |  |
| NH4OH*NH4OH         | 0.507691  |  |  |  |  |  |
| MegaPower*MegaPower | -0.258493 |  |  |  |  |  |
| N2*N2               | -0.207414 |  |  |  |  |  |
| N2*MegaPower        | 0.153237  |  |  |  |  |  |





III

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